What is claimed is:

1. A low voltage micro switch comprising:

a substrate having an actuating space formed by etching at a certain area therein:

an actuating unit having a piezoelectric material extended in a cantilever beam shape from a portion of the substrate to the actuating space of the substrate and a bias electrode;

a conductive signal line extendedly formed at a certain interval from one side of the substrate and having a disconnected portion;

- a supporting unit connected to the actuating unit, positioned in the actuating space, and moving according to actuation of the actuating unit;
- a switching unit formed at the supporting unit and connecting or disconnecting the disconnected portion of the conductive signal line according to movement of the supporting unit; and

one or more ground units formed at the substrate.

2. The switch of claim 1, wherein the actuating space has a groove form with a certain depth in a portion of the substrate.

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- 3. The switch of claim 1, wherein the actuating space is formed penetratingly in a portion of the substrate.
- 4. The switch of claim 1, wherein the switching unit is made of a conductor material.

5. The switch of claim 1, wherein the actuating unit includes four cantilever portions formed at certain intervals, and the supporting unit includes a plate portion forming the switching unit and four connection portions connecting the plate portion and four cantilever portions.

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6. The switch of claim 1, wherein the actuating unit has one cantilever portion having a certain length, and the supporting unit includes a plate portion forming the switching unit and a connection portion connecting the plate portion and the cantilever portion.

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- 7. The switch of claim 6, wherein there are two or three connection portions.
- 8. The switch of claim 1, wherein the actuating unit includes two cantilever portion formed at a certain interval, and the supporting unit includes a plate portion positioned between the two cantilever portions and forming the switching unit and a connection portion connecting the plate portion and the two cantilever portions.
- 9. The switch of claim 8, wherein there are two or more connection portions connecting the plate portion and the cantilever portions.
 - 10. The switch of claim 1, wherein the actuating unit includes two cantilever portions formed at a certain interval, and the supporting unit includes a plate portion forming the switching unit and a connection portion connecting one

side of the plate portion and the cantilever portions.

11. A low voltage micro switch comprising:

a substrate having an actuating space formed by etching at a certain area therein:

an actuating unit having a piezoelectric material extended in a cantilever beam shape from a portion of the substrate to the actuating space of the substrate and a bias electrode;

a conductive signal line extendedly formed at a certain interval from one side of the substrate;

a supporting unit connected to the actuating unit, having a connection electrode connected to the substrate, and moving according to actuation of the actuating unit in the actuating space;

a capacitor unit formed on the connection electrode of the supporting unit and contacted to or separated from the conductive signal line according to movement of the supporting unit; and

one or more ground units formed at the substrate.

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- 12. The switch of claim 11, wherein the actuating unit includes four cantilever portions formed at certain intervals, and the supporting unit includes a plate portion forming the capacitor unit and four connection portions connecting the plate portion and four cantilever portions.
- 13. The switch of claim 11, wherein the actuating unit has one cantilever portion having a certain length, and the supporting unit includes a plate

portion forming the capacitor unit and a connection portion connecting the plate portion and the cantilever portion.

- 14. The switch of claim 13, wherein there are two or three connection portions.
 - 15. The switch of claim 11, wherein the actuating unit includes two cantilever portion formed at a certain interval, and the supporting unit includes a plate portion positioned between the two cantilever portions and forming the capacitor unit and a connection portion connecting the plate portion and the two cantilever portions.
 - 16. The switch of claim 15, wherein there are two or more connection portions connecting the plate portion and the cantilever portions.

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17. The switch of claim 11, wherein the actuating unit includes two cantilever portions formed at a certain interval, and the supporting unit includes a plate portion forming the capacitor unit and a connection portion connecting one side of the plate portion and the cantilever portions.

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- 18. The switch of claim 11, wherein the capacitor unit comprises:
- a first metallic layer formed at an upper portion of the connection electrode of the supporting unit;
 - a dielectric layer formed on the first metallic layer; and
 - a second metallic layer formed on the dielectric layer.

19. The switch of claim 18, wherein the supporting unit is formed as a high resistance silicon layer.